What is claimed is:

1. A method of performing a predetermined processing for an electric circuit on a circuit-constituting member by employing plasma generated by employing a high frequency electric voltage on specified gases introduced into a vacuum space, comprising the step of:

starting said predetermined processing for said electric circuit on said circuit-constituting member when it is confirmed that said plasma is brought into a stable condition thereof after starting of generation of said plasma.

2. The method as set forth in claim 1, further comprising the step of:

detecting a predetermined time lapse after the starting of generation of said plasma to thereby confirm that said stable condition of said plasma is reached.

3. The method as set forth in claim 1, wherein said method further comprises the steps of:

transferring said circuit-constituting member from a first position where said plasma is generated to a second position where said plasma is not generated before said generation of plasma is started; and

returning said circuit-constituting member

from said second position to said first position when said stable condition of plasma is reached.

4. The method as set forth in claim 2, wherein said method further comprises the steps of:

transferring said circuit-constituting member from a first position where said plasma is generated to a second position where said plasma is not generated before said generation of plasma is started; and

returning said circuit-constituting member from said second position to said first position when said stable condition of plasma is reached.

5. The method as set forth in claim 1, wherein said method further comprises the steps of:

covering said circuit-constituting member against a position where said plasma is generated before said generation of plasma is started; and

uncovering said circuit-constituting member to thereby expose said circuit-constituting member to said plasma at the position where said plasma is generated when said stable condition of plasma is reached.

6. The method as set forth in claim 2, wherein said method further comprises the steps of:

covering said circuit-constituting member

against a position where said plasma is generated before said generation of plasma is started; and

uncovering said circuit-constituting member to thereby expose said circuit-constituting member to said plasma at the position where said plasma is generated when said stable condition of plasma is reached.

7. The method as set forth in claim 3, wherein said method further comprises the steps of:

vacuumizing said first position to a predetermined low vacuum condition before said generation of plasma is started;

vacuumizing further said first position to a predetermined high vacuum condition; and

implementing said returning of said circuit-constituting member from said second position to said first position at the high vacuum condition.

8. The method as set forth in claim 4, wherein said method further comprises the steps of:

vacuumizing said first position to a predetermined low vacuum condition before said generation of plasma is started;

vacuumizing further said first position to a predetermined high vacuum condition; and

implementing said returning of said circuit-

constituting member from said second position to said first position at the high vacuum condition.

9. A method of controlling a motion of an apparatus for performing a predetermined processing for an electric circuit on a circuit-constituting member by employing plasma generated by a plasma-generation means which employs a high frequency electric voltage on specified gases introduced into a vacuum space, comprising the steps of:

detecting a stable condition of said plasma by a detecting means when generation of said plasma is started by said plasma generation means; and

starting said predetermined processing for said electric circuit on said circuit-constituting member when said detecting means detects that said plasma is brought into a stable condition thereof.

10. A method of controlling the motion of an apparatus for performing a predetermined processing for an electric circuit on a circuit-constituting member including a hollow plasma generative portion in which plasma is generated, a hollow waiting portion for a processed object consisting of a circuit-constituting member, said portion being operatively connected to the plasma generative portion, and a member-transferring

means for supporting thereon said circuit-constituting member and for transferring said processed object to each of said waiting portion and said plasma generative portion, said apparatus for performing said predetermined processing for said electric circuit on said circuit-constituting member by said plasma when said circuit-constituting member is transferred by said member-transferring means from said hollow waiting portion to said plasma generative portion, wherein said controlling method comprises the steps of:

positioning said circuit-constituting member at said hollow waiting portion when generation of said plasma is started in said plasma generative portion; and

transferring said circuit-constituting member from said hollow waiting portion to said plasma generative portion by said member-transferring means when said plasma in said plasma generative portion is brought into a stable condition thereof after the starting of generation of said plasma.

11. A method of controlling the motion of an apparatus for performing a predetermined processing for an electric circuit on a circuit-constituting member including a hollow plasma generative portion in which plasma is generated, a plasma generating means for generating plasma at a first predetermined position in

said plasma generative portion, a member-holding means for holding said circuit-constituting member at a second predetermined position opposing said first predetermined position in said plasma generative portion, a member-coverage means for applying removable coverage to said circuit-constituting member between said first predetermined position where said plasma is generated by said plasma generating means and said second predetermined position where said circuit-constituting member is held by said member-holding means, said apparatus for performing said predetermined processing for said electric circuit on said circuit-constituting member by said plasma, wherein said controlling method comprises the steps of:

effecting application of said coverage to said circuit-constituting member when generation of said plasma by said plasma generating means is started; and

removing said coverage from said circuit-constituting member when said plasma generated by said plasma generating means is brought into a stable condition thereof after the starting of generation of said plasma.

12. An apparatus for performing a predetermined processing for an electric circuit on a circuit-constituting member by employing plasma generated by

employing a high frequency electric voltage on specified gases introduced into a vacuum space, comprising:

a plasma generating means for generating said plasma;

a stability detecting means for detecting a stable condition of said plasma upon being started to generate by said plasma generating means; and,

a processing controlling means for controlling start of said predetermined processing for said electric circuit on said circuit-constituting member when said detecting means detects said stable condition of said plasma.

13. An apparatus for performing a predetermined processing for an electric circuit on a circuit-constituting member by employing plasma generated by employing a high frequency electric voltage on specified gases introduced into a vacuum space, comprising:

a plasma generative portion defined to have an interior space thereof in which said plasma is generated;

a hollow member-waiting portion defined to have an interior thereof operatively connected to said plasma generative portion;

a member-transferring means for supporting thereon said circuit-constituting member while permitting said circuit-constituting member to be freely transferred

to said member-waiting portion and said plasma generative portion;

a stability detecting means for detecting a stable condition of said plasma upon being started to generate in said plasma generative portion; and,

a processing controlling means for permitting said circuit-constituting member to be positioned in said hollow member-waiting portion by said member-transferring means when generation of said plasma is started in said plasma generative portion and for permitting said circuit-constituting member to be transferred from said hollow member-waiting portion to said plasma generative portion by said member-transferring means when stability detecting means detects said stable condition of said plasma.

14. An apparatus for performing a predetermined processing for an electric circuit on a circuit-constituting member by employing plasma generated by employing a high frequency electric voltage on specified gases introduced into a vacuum space, comprising:

a plasma generative portion defined to have an interior space thereof in which said plasma is generated;

a plasma generating means for generating plasma at a predetermined position in said plasma generative portion;

a member-holding means for holding said circuit-constituting member in said plasma generative portion at a different position opposing said predetermined position where said plasma is generated by said plasma generating means;

a member-coverage means for removably covering said circuit-constituting member between said predetermined position where said plasma is generated by said plasma generating means and said different position where said circuit-constituting member is held by said member-holding means;

a stability detecting means for detecting a stable condition of said plasma upon being started to generate by said plasma generating means; and,

a processing controlling means for permitting said circuit-constituting member to be covered by said member-coverage means when said plasma generating means starts to generate said plasma, and for permitting said member-coverage means to remove covering of said circuit-constituting member when stability detecting means detects said stable condition of said plasma.

15. The apparatus as set forth in claim 10, further comprising a vacuum adjusting means for adjustably varying a degree of vacuum prevailing in said plasma generative portion, and wherein said processing

controlling means permits said vacuum adjusting means to produce a predetermined low vacuum condition in said plasma generative portion when said plasma starts to be generated in said plasma generative portion, said processing controlling means further permitting said vacuum adjusting means to produce a predetermined high vacuum condition in said plasma generative portion before said circuit-constituting member is transferred to said plasma generative portion when said stable condition of said plasma is reached.

16. The apparatus as set forth in claim 13, wherein at least when said circuit-constituting member is transferred from said hollow member-waiting portion to said plasma generative portion, said hollow member-waiting portion is held at a predetermined low vacuum condition less than a vacuum condition prevailing in said plasma generative portion.

17. The apparatus as set forth in claim 15, wherein at least when said circuit-constituting member is transferred from said hollow member-waiting portion to said plasma generative portion, said hollow member-waiting portion is held at a predetermined low vacuum condition less than a vacuum condition prevailing in said plasma generative portion.

18. The apparatus as set forth in claim 12, wherein said stability detecting means detects said stable condition of said plasma in response to detection of a predetermined time lapse from a start of generation of said plasma.

19. The apparatus as set forth in claim 13, wherein said stability detecting means detects said stable condition of said plasma in response to detection of a predetermined time lapse from a start of generation of said plasma.

20. The apparatus as set forth in claim 14, wherein said stability detecting means detects said stable condition of said plasma in response to detection of a predetermined time lapse from a start of generation of said plasma.

21. The apparatus as set forth in claim 15, wherein said stability detecting means detects said stable condition of said plasma in response to detection of a predetermined time lapse from a start of generation of said plasma.

22. The apparatus as set forth in claim 16,

wherein said stability detecting means detects said stable condition of said plasma in response to detection of a predetermined time lapse from a start of generation of said plasma.

23. The apparatus as set forth in claim 17, wherein said stability detecting means detects said stable condition of said plasma in response to detection of a predetermined time lapse from a start of generation of said plasma.

24. An apparatus for controlling a motion of a circuit-processing performing apparatus in which a predetermined processing for an electric circuit is processed on a circuit-constituting member by plasma generated by employing a high frequency electric voltage on specified gases introduced into a vacuum space, wherein said controlling apparatus comprises:

a stability detecting means for detecting a stable condition of said plasma that has started to be generated; and,

a processing controlling means for starting said predetermined processing for said electric circuit to be processed on said circuit-constituting member after said stability detecting means detects said stable condition of said plasma.

25. An apparatus for controlling a motion of a circuit-processing performing apparatus provided with a hollow plasma-generative portion defined to have an interior thereof in which plasma is generated, a hollow member-waiting portion defined to have an interior thereof operatively connected to said interior of said plasma-generative portion, and a member-transferring means for supporting thereon a processed object consisting of a circuit-constituting member while permitting said circuit-constituting member to be transferred to said member-waiting portion and said plasma-generative portion, said circuit-constituting member being processed by said plasma when said circuit-constituting member is transferred from said member-waiting portion to said plasma-generative portion, wherein said controlling apparatus comprises:

a stability detecting means for detecting a stable condition of said plasma that has started to be generated in said plasma-generative portion; and,

a processing controlling means for permitting said circuit-constituting member to be positioned by said member-transferring means in said member-waiting portion when said plasma starts to be generated in said plasma-generative portion, and for permitting said circuit-constituting member to be transferred by said member-

transferring means from said member-waiting portion to said plasma-generative portion when said stability detecting means detects said stable condition of said plasma.

26. An apparatus for controlling a motion of a circuit-processing performing apparatus provided with a hollow plasma-generative portion defined to have an interior thereof in which plasma is generated, a plasma generating means for generating said plasma at a predetermined position in said hollow plasma-generative portion, a member-holding means for holding said circuit-constituting member in said plasma-generative portion at a position opposing said predetermined position where said plasma is generated by said plasma generating means, and a member-coverage means for removably covering said circuit-constituting member between said predetermined position where said plasma is generated by said plasma generating means and said position where said member-holding means holds said circuit-constituting member, said circuit-processing performing apparatus processing said circuit-constituting member by said plasma, wherein said controlling apparatus comprises:

a stability detecting means for detecting a stable condition of said plasma that has started to be generated by said plasma generating means; and,

a processing controlling means for permitting said member-coverage means to cover said circuit-constituting member when said plasma generating means starts to generate said plasma, and for permitting said member-coverage means to remove covering from said circuit-constituting member when said stability detecting means detects said stable condition of said plasma.

27. An information storage medium for storing a program freely read by an electronic computer that controls a motion of a circuit-processing performing apparatus in which a predetermined processing for an electric circuit is processed on a circuit-constituting member by plasma generated by employing a high frequency electric voltage on specified gases introduced into a vacuum space, wherein said information storage medium stores a program for being executed by said electronic computer to thereby start processing of said predetermined processing for said electric circuit on said circuit-constituting member after said plasma that has started to be generated is brought into a stable condition.

28. An information storage medium for storing a program freely read by an electronic computer that controls a motion of a circuit-processing performing

apparatus provided with a hollow plasma-generative portion defined to have an interior thereof in which plasma is generated, a hollow member-waiting portion defined to have an interior thereof operatively connected to said interior of said plasma-generative portion, and a member-transferring means for supporting thereon a processed object consisting of a circuit-constituting member while permitting said circuit-constituting member to be freely transferred to said member-waiting portion and said plasma-generative portion, said circuit-constituting member being processed by said plasma when said circuit-constituting member is transferred from said member-waiting portion to said plasma-generative portion,

wherein said information storage medium stores a program for being executed by said electronic computer thereby permitting said member-transferring means

to position said circuit-constituting member in said member-waiting portion when said plasma starts to be generated in said plasma-generative portion, and

to transfer said circuit-constituting member from said member-waiting portion to said plasma-generative portion when said plasma that has started to be generated is brought into a stable condition thereof.

29. An information storage medium for storing a program freely read by an electronic computer that

controls a motion of a circuit-processing performing apparatus provided with a hollow plasma-generative portion defined to have an interior thereof in which plasma is generated, a plasma generating means for generating said plasma at a predetermined position in said hollow plasma-generative portion, a member-holding means for holding said circuit-constituting member in said plasma-generative portion at a position opposing said predetermined position where said plasma is generated by said plasma generating means, and a member-coverage means for removably covering said circuit-constituting member between said predetermined position where said plasma is generated by said plasma generating means and said position where said member-holding means holds said circuit-constituting member, said circuit-processing performing apparatus processing said circuit-constituting member by said plasma,

wherein said information storage medium stores a program for being executed by said electronic computer thereby permitting said member-coverage means

to cover said circuit-constituting member when said plasma generating means starts to generate said plasma, and

to remove covering from said circuit-constituting member when said plasma that has started to be generated by said plasma generating means is brought

into a stable condition thereof.